

Performance Control and Application of ZnO-Based P-N Junction Piezoelectric Devices

Xudong Shen¹, Dongying Liu², Li Zhao^{3*}

¹Center for Soft Machines and Smart Devices, Huanjiang Laboratory, Zhuji 311800, China

²School of Civil Engineering and Transportation, Guangzhou University, Guangzhou 510006, China

³School of Civil Engineering and Architecture, Zhejiang University of Science & Technology, Hangzhou 310023, China

*Corresponding author: Li Zhao, zhaoli@zust.edu.cn

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Abstract: Zinc oxide (ZnO), as a broadband gap semiconductor material, exhibits unique physical and chemical properties that make it highly suitable for optoelectronics, piezoelectric devices, and gas-sensitive sensors, showing significant potential for various applications. This paper focuses on the regulation and application of ZnO-based p-n junctions and piezoelectric devices. It discusses in detail the preparation of ZnO materials, the construction of p-n junctions, the optimization of piezoelectric device performance, and its application in various fields. By employing different preparation methods and strategies, high-quality ZnO thin films can be grown, and effective control of p-type conductivity achieved. This study provides both a theoretical foundation and technical support for controlling the performance of ZnO-based piezoelectric devices, as well as paving new pathways for the broader application of ZnO materials.

Keywords: ZnO; p-n junction; Piezoelectric device; Performance control; Application

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1. Introduction

ZnO is an excellent performance II–IV wide bandgap semiconductor material, with a bandgap width of up to 3.37 eV at room temperature and an exciton binding energy of 60 meV, which is significantly higher than other wide bandgap semiconductors such as gallium nitride (GaN) (25 meV) and zinc selenide (ZnSe). These properties make ZnO an ideal choice for short-wavelength optoelectronic devices and ultraviolet emission materials. ZnO also has a high electron saturation drift velocity, excellent thermal stability, and good piezoelectric properties, making it highly suitable for applications in piezoelectric devices, transparent electrodes, photocatalysis, thin-film transistors, and other fields with broad prospects ^[1]. Based on this, research into the performance control and application of ZnO p-n junctions in piezoelectric devices holds significant scientific and practical value.

2. Preparation of ZnO materials and construction of p-n junctions

2.1. Preparation of ZnO materials

ZnO as an important semiconductor material, in optoelectronics, piezoelectric, sensing, and other fields has broad application prospects. Its unique physical and chemical properties, such as high electron mobility, wide band gap, high exciton binding energy, and good chemical and thermal stability, have made ZnO a research hotspot ^[2]. To prepare high-quality ZnO materials, researchers have developed a variety of preparation methods, including the precipitation method, sol-gel method, microemulsion method, and hydrothermal (solvothermal) method.

2.1.1. The precipitation method

Precipitation is one of the most commonly used methods for ZnO preparation, primarily divided into direct precipitation and uniform precipitation. Precipitation involves adding a suitable precipitant (such as ammonia, ammonium bicarbonate, etc.) to a soluble zinc salt solution, which reacts with zinc (OH)₂ or Zn₂(OH)₂CO₃ precursors ^[3]. After washing, drying, and calcination steps, ZnO nanoparticles are obtained. For example, reacting zinc nitrate (Zn(NO₃)₂) solution with sodium hydroxide (NaOH) generates zinc hydroxide (Zn(OH)₂) precipitate, which, after heat treatment, produces ZnO nanoparticles. This method is simple, and low-cost, but results in a wide particle size distribution, requiring further control of particle size.

The uniform precipitation method involves adding urea and other slow-release OH⁻ precipitants to a soluble zinc salt solution. By carefully controlling the reaction temperature and pH, the precipitation process becomes more even, resulting in a narrower particle size distribution of ZnO nanoparticles ^[4]. This method produces ZnO particles with better dispersion and more uniform size distribution. However, the preparation process is relatively complex, and the cost is higher.

2.1.2. The sol-gel method

The sol-gel method involves dissolving zinc alkoxide or inorganic salts in alcohol or water to form a sol, which is then aged, dried, and calcined to obtain ZnO materials. This method allows for the preparation of ZnO materials with high purity, good uniformity, and controllable particle size. Nevertheless, the sol-gel method still faces some challenges, such as the need for strict control of reaction conditions during preparation to avoid cracking or aggregation of the gel.

2.1.3. The microemulsion method

The microemulsion method uses surfactants to form a microemulsion of two mutually immiscible liquids, such as water and oil. Chemical reactions occur within the microemulsion droplets to generate ZnO nanoparticles. The particle size distribution of ZnO nanoparticles prepared by this method is uniform, and both particle size and morphology can be controlled by adjusting the composition of the microemulsion and the reaction conditions ^[5]. However, the preparation process of the microemulsion method is complex and requires a large amount of surfactants, which increases both the cost and environmental burden.

2.1.4. Hydrothermal (solvothermal) method

The hydrothermal (solvothermal) method involves high temperature and pressure, using water or organic solvents as the reaction medium. In this method, hydrolysis or Reduction-Oxidation (REDOX) reactions of zinc salts occur, generating ZnO nanoparticles. The ZnO particles prepared using this method have high crystallinity and controllable particle size, and their morphology and properties can be adjusted by controlling reaction temperature, pressure, and

reaction time ^[6]. Nonetheless, the hydrothermal (solvothermal) method requires high-temperature and high-pressure reaction conditions, necessitating significant equipment investment and carrying certain safety risks.

2.2. The construction of the p-n junction

The p-n junction is the basis of semiconductor devices. By constructing a p-n junction, the regulation of the electrical properties of semiconductor materials and the diversification of device functions can be realized. For ZnO materials, due to its intrinsic characteristics as an n-type semiconductor, the preparation of high-quality p-type ZnO is key to the successful construction of ZnO-based p-n structures.

2.2.1. Preparation of p-type ZnO

To realize the p-type doping of ZnO, researchers have tried a variety of doping elements and doping methods. Among them, group V elements such as nitrogen (N), phosphorous (P), and arsenic (As) are the most commonly used p-type dopants. However, due to the strong self-compensation effect and donor doping effect in ZnO, the preparation of p-type ZnO has always been a difficult problem ^[7]. In recent years, researchers have successfully prepared ZnO materials with stable p-type conductivity by using co-doping, double-doping, and multi-layer structures. For example, by nitrogen-aluminum (N-Al) doping, the donor can inhibit ZnO defects, and improve the efficiency of p-type doping. By constructing a zinc oxide/magnesium zinc oxide (ZnO/MgZnO) multilayer structure, the band engineering effect of MgZnO can be used to improve the carrier concentration and mobility of p-type ZnO.

2.2.2. Construction method of p-n junction

After the preparation of high-quality p-type and n-type ZnO materials, ZnO-based p-n junctions can be constructed by various methods. Some of the most commonly used methods are ion implantation, diffusion, epitaxial growth technology, etc. Ion implantation is a p-type or n-type dopant ion implantation into the ZnO materials, through annealing treatment the dopant atoms diffusion in the ZnO and lattice position, to realize the construction of a p-n junction ^[8]. Diffusion law is p-type or n-type doping source contact with ZnO materials, through high-temperature diffusion of dopant atoms into the ZnO lattice, forming a p-n junction. The epitaxial growth rule is to directly grow p-type and n-type ZnO thin films on an appropriate substrate by vapor deposition or molecular beam epitaxial technology, thereby forming p-n junctions.

In addition to the above method, laser doping, chemical vapor deposition, and electrochemical deposition technology can be used for the construction of the ZnO p-n junction. Each of these methods has its advantages and disadvantages, and it is necessary to choose the appropriate construction method according to the specific application requirements and material properties.

3. Performance optimization strategies for ZnO-based p-n junction piezoelectric devices

3.1. Optimization of material preparation

3.1.1. Growth of high-quality ZnO films

High-quality ZnO films are the basis for the realization of high-performance p-n junction piezoelectric devices. To obtain high-quality ZnO thin films, there is a need to optimize the growing conditions, such as temperature, pressure, reactant concentration, etc., to control the crystallization of the film quality, surface morphology, and

defect density^[9]. Furthermore, adopting advanced technology of thin film growth, such as molecular beam epitaxy (MBE), pulsed laser deposition (PLD), and chemical vapor deposition (CVD), etc., can further improve the quality of ZnO thin films and uniformity.

3.1.2. Doping control of p-type and n-type ZnO

To achieve p-type and n-type ZnO doping, it is necessary to accurately control the type, concentration, and distribution of doping elements. For P-type doping, the commonly used elements include N, P, As, etc., while for N-type doping, aluminum (Al), gallium (Ga), and other elements are usually used. Optimizing the doping process, such as adjustment of doping source concentration, reaction time and temperature, etc., can achieve the effective control of doping elements and uniform distribution, to improve the conductivity and stability of ZnO thin films.

3.2. Optimization of structural design

3.2.1. Optimization of p-n junction structure

The structural design of the p-n junction has an important impact on the performance of the device. By optimizing the interface quality, thickness, and doping concentration of the p-n junction, the band structure, carrier concentration, and mobility of the device can be adjusted, to improve the photoelectric conversion efficiency and piezoelectric response sensitivity of the device. Additionally, the use of multilayer structures or heterogeneous structures, such as ZnO/MgZnO multilayer structures or ZnO with other semiconductor materials heterostructures, can further expand the function and application range of the devices.

3.2.2. Design of piezoelectric layer

The piezoelectric layer is the core part of ZnO-based p-n junction piezoelectric devices, and its performance directly affects the piezoelectric response and energy conversion efficiency of the device. To optimize the performance of the piezoelectric layer, it is necessary to select the appropriate piezoelectric material and optimize the thickness and orientation of the piezoelectric layer and other parameters. Moreover, the sensitivity and response speed of the piezoelectric layer can be further improved by introducing microstructures or nanostructures, such as nanowires, nanorods, or nanopores.

3.3. Optimization of doping modification

3.3.1. Co-doping and double doping strategies

Co-doping and double doping strategies are effective methods to optimize the performance of ZnO-based p-n junction piezoelectric devices. By introducing two or more doping elements at the same time, the band structure of ZnO can be accurately controlled, and the conductivity and stability of the device can be improved. For example, N-Al co-doping can suppress the donor defects in ZnO and improve the p-type doping efficiency. Meanwhile, gallium-nitrogen (Ga-N) co-doping can improve the conductivity and stability of n-type ZnO simultaneously^[10].

3.3.2. Control of the concentration and distribution of the doped elements

The concentration and distribution of doping elements have an important impact on the properties of ZnO-based p-n junction piezoelectric devices. By precisely controlling the concentration and distribution of doping elements, the device performance can be fine-tuned^[11]. For example, by adjusting the concentration of p-type doping elements, the electrical conductivity and piezoelectric response sensitivity of the device can be optimized. By controlling the distribution of the doping elements in the ZnO films, the uniformity and stability of the device performance can be improved.

3.4. Optimization of interface engineering

3.4.1. Improvement of interface quality

Interface quality is one of the key factors affecting the performance of ZnO-based p-n junction piezoelectric devices. The interface quality and stability of the device can be improved by optimizing the material matching at the interface and reducing interface defects and contamination ^[12]. For example, the interface quality between ZnO and other materials can be improved by using an appropriate buffer layer or transition layer. By cleaning and passivation treatment, the contamination and defects at the interface can be reduced and the performance and reliability of the device can be improved.

3.4.2. Regulation of interface potential barrier

The interface potential barrier is an important factor affecting the photoelectric conversion efficiency and piezoelectric response sensitivity of ZnO-based p-n junction piezoelectric devices. By adjusting the height and width of the interface barrier, the device performance can be fine-tuned ^[13]. For example, by adjusting the doping concentration and band structure at the p-n junction interface, the height and width of the interface barrier can be optimized, so as to improve the photoelectric conversion efficiency and piezoelectric response sensitivity of the device.

3.4.3. Improvement of interfacial charge transport

Interfacial charge transport is one of the key factors affecting the response speed and stability of ZnO-based p-n junction piezoelectric devices. By optimizing the charge transport channel at the interface and reducing the obstruction of charge transport, the response speed and stability of the device can be improved. For example, by introducing a conductive layer or electrode materials with high conductivity, the performance of charge transfer on the interface can be improved ^[14]. Additionally, optimizing the interface morphology and microstructure can reduce the obstacles and scattering charge transfer, improve the response speed, and stability of the device.

4. Application paths of ZnO-based p-n junction piezoelectric devices

4.1. Energy conversion field

In the field of energy conversion, ZnO-based p-n junction piezoelectric devices have shown their unique advantages and application potential. Among them, piezoelectric energy harvesting is one of the important applications in this field. When these devices by external force, such as deformation, stress, vibration, or they can use the piezoelectric effect converts mechanical energy efficiently to electricity. Not only does this conversion mechanism provide a novel and sustainable power solution for low-power electronic devices, but through continuous device structure design and material property optimization, we are expected to achieve more efficient and stable piezoelectric energy harvesting ^[15].

Imagine if ZnO p-n junction piezoelectric devices were integrated into wearable devices. These devices could harness the small mechanical energy generated by body movements to collect energy and power themselves. This would not only address the issue of limited battery life in wearable devices but also greatly enhance the user experience, allowing these devices to accompany users for longer periods while recording every moment of their lives.

Furthermore, ZnO-based p-n junction piezoelectric devices hold great potential in the field of self-powered sensors. By combining the piezoelectric and optical properties of ZnO, we can develop a new type of self-powered sensor. Such a sensor could respond to external forces or light stimuli, generating piezoelectric and optical signals to enable dual detection functionality. This dual mechanism would not only improve the sensitivity and accuracy

of the sensor but also make it capable of reliable measurements in more complex and dynamic environments.

In environmental monitoring and structural health monitoring, these self-powered sensors could play a significant role. They would enable real-time monitoring of environmental changes or structural states, providing precise and timely data to support policymakers and researchers in related fields.

4.2. The field of intelligent sensing

ZnO-based p-n junction piezoelectric devices have also shown extraordinary potential and value in the field of intelligent sensing. Especially in the field of pressure and strain sensing, their high sensitivity makes it possible to accurately measure small pressures and strains. Through careful sensor structure design and material performance optimization, we can aim for industrial automation, aerospace, automobile manufacturing, and other areas of the high precision requirement to provide reliable sensor solutions. These sensors can be applied in real-time monitoring and feedback for all kinds of stress and strain data, for the related fields of production, research and development, and safety monitoring to provide strong technical support.

Additionally, the application of ZnO-based p-n junction piezoelectric devices in the field of biosensing is also attracting attention. Thanks to their good biocompatibility and chemical stability, these devices can achieve good interaction and recognition with biomolecules, cells or organisms. Through surface modification or the introduction of biometric elements, we can develop biosensors with specific recognition and detection functions. These sensors have broad application prospects in fields related to human health, such as disease diagnosis, drug screening, and food safety monitoring. They can achieve accurate and rapid detection of biological samples, and provide powerful data support for medical research and clinical applications.

4.3. Biomedical field

ZnO-based p-n junction piezoelectric devices have also shown great application potential in the biomedical field. Due to their small size, high sensitivity and excellent biocompatibility, these devices can be safely implanted into organisms to achieve energy harvesting and real-time monitoring of physiological parameters. For example, in cardiac surgery or vascular therapy, we can implant devices into the heart or blood vessels and harvest the energy generated by the beating heart or blood flow, while monitoring the physiological state of the heart or blood vessels in real time, providing doctors with valuable diagnostic and therapeutic information. Moreover, ZnO-based p-n junction piezoelectric devices can also be used as core components in biomedical implants to provide electrical support or signal transmission functions for the implants. In high-end implants such as artificial heart valves and nerve stimulators, these devices can use the piezoelectric effect to achieve efficient energy conversion and stable signal transmission, ensuring long-term stable operation and precise control of implants, and providing a strong guarantee for the rehabilitation and quality of life of patients.

5. Conclusion

In summary, ZnO-based p-n junction piezoelectric devices show great application potential in the fields of energy conversion, intelligent sensing, and biomedicine due to their unique piezoelectric effects and photoelectric properties. However, in order to achieve efficient, stable, and reliable applications of these devices, it is necessary to optimize the material preparation, structure design, doping modification, and interface engineering of these devices to realize the fine control and significant improvement of device performance, which provides strong support for the wide application of ZnO-based p-n junction piezoelectric devices.

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Disclosure statement

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